

SAT
4
5-1602

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TATSUURA, Yasuhiro SATO, Minquan TIAN and Prior Group Art Unit: 1741
Lyong Sun PU

Application No.: Rule 53(b) Divisional Application of
U.S. Application No. 09/571,864

Prior Examiner: E. Wong

Filed: February 26, 2002

Docket No.: 106200.01

For: METHOD FOR ELECTRODEPOSITED FILM FORMATION, METHOD FOR
ELECTRODE FORMATION, AND APPARATUS FOR ELECTRODEPOSITED FILM
FORMATION

INFORMATION DISCLOSURE STATEMENT

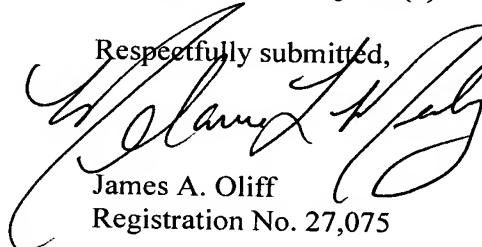
Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. The references were cited by or submitted to the Office in parent application No. 09/571,864, filed May 16, 2000, which is relied upon for an earlier filing date under 35 U.S.C. §120. Thus, copies of these references are not attached. 37 CFR §1.98(d).

Respectfully submitted,


James A. Oliff
Registration No. 27,075

Melanie L. Mealy
Registration No. 40,085

JAO:MLM/jam

Date: February 26, 2002
OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461

Form PTO-1449
(REV. 8-83)US Dept. of Commerce
PATENT & TRADEMARK OFFICE

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

ATTY DOCKET NO.
106200.01APPLICATION NO.
Rule 53(b) Continuing
Application of U.S.
Application No. 09/571,864
Filed May 16, 2000APPLICANTS
Satoshi TATSUURA, Yasuhiro SATO, Minquan TIAN, and Lyong Sun PUFILING DATE
February 26, 2002

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	4,349,583	09/1982	KULYNYCH et al.		
	4,217,183	08/1980	MELCHER et al.		

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	Gutfield et al., <u>Electrochemical microfabrication by laser-enhanced photothermal processes</u> , IBM J. Res. Develop., Vol. 42, No. 5, 1998, pp. 639-652.
	Chichkov et al., <u>Femtosecond, picosecond and nanosecond laser ablation of solids</u> , Applied Physics A-63, 1996, pp. 109-115.
	Obara et al., <u>Laser Engineering Optics</u> , Kyoritsu Shuppan, 1998, pp. 130-133.
	GUTFELD et al., "Electrochemical Microfabrication by Laser-Enhanced Photothermal Processes," J. Res. Develop., Vol. 42, No. 5, pp. 639-652, September 1998.

EXAMINER

DATE CONSIDERED

Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.